AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A high-function photocatalyst having its surface partially covered with a polymer having an anionic group, said polymer leaving uncovered photocatalyst surface,

wherein the polymer having an anionic group attracts pollutant materials having a positive charge to the photocatalyst surface, and the polymer is selected from the group consisting of poly(fluorine-substituted sulfonic acid), poly(fluorine containing carboxylic acid), polystyrene sulfonic acid, and polyvinyl sulfonic acid, and

wherein said partially covered surface is prepared by applying a polymer solution in an amount of 0.05 to 5-ml 0.4 ml with a 5% by weight solution to the photocatalyst surface per gram of the photocatalyst.

whereby the polymer having an anionic group attracts pollutant materials having a positive charge so close to said photocatalyst surface as to promote photocatalytic decomposition of the pollutant materials.

- 2. (Original) The high-function photocatalyst according to claim 1, wherein the photocatalyst is a linear polymer.
- 3. (Original) The high-function photocatalyst according to claim 1 or 2, wherein the photocatalyst is in a form of a fine powder with particle size of 0.04 to 1 μm .

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4. (Cancelled)

5. (Previously Presented) The high-function photocatalyst according

to claim 1 or 2, wherein the photocatalyst is spherical.

6. (Previously Presented) The high-function photocatalyst according

to claim 1 or 2, wherein the photocatalyst is immobilized on a substrate.

7. (Currently Amended) A method of manufacturing a high-function

photocatalyst comprising the steps of adding a spherical photocatalyst into a

solution having a linear polymer having an anionic group dissolved in a

solvent, stirring, and drying, said polymer leaving partially uncovered

photocatalyst surface, wherein the polymer having an anionic group attracts

pollutant materials having a positive charge to the photocatalyst surface, and

the polymer is selected from the group consisting of poly(fluorine-substituted

sulfonic acid), poly(fluorine containing carboxylic acid), polystyrene sulfonic

acid, and polyvinyl sulfonic acid, and wherein said partially uncovered

photocatalyst surface is prepared by applying a polymer solution in an amount

of 0.05 to 5 ml 0.4 ml with a 5% by weight solution to the photocatalyst surface

per gram of the photocatalyst.

8. (Previously Presented) A method of manufacturing a high-function

photocatalyst comprising the steps of immobilizing a photocatalyst on a

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substrate of a film, applying to a substrate surface a solution dissolving a polymer having an anionic group in an amount of 0.1 to 1 ml of a 5% by weight

solution per substrate surface area of 20 cm², and drying, wherein the polymer

having an anionic group attracts pollution materials having a positive charge to

a photocatalyst surface, and the polymer is selected from the group consisting

of poly(fluorine-substituted sulfonic acid), poly(fluorine containing carboxylic

acid), polystyrene sulfonic acid, and polyvinyl sulfonic acid.

9-11. (Cancelled)

12. (Previously Presented) The high-function photocatalyst according

to claim 1, wherein the photocatalyst is selected from the group consisting of

titanium dioxide, zinc oxide, zirconium oxide and tungsten oxide.

13. (Previously Presented) The method according to claim 7, wherein

the photocatalyst is selected from the group consisting of titanium dioxide, zinc

oxide, zirconium oxide and tungsten oxide.

14. (Previously Presented) The method according to claim 8, wherein

the photocatalyst is selected from the group consisting of titanium dioxide, zinc

oxide, zirconium oxide and tungsten oxide.

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15. (Currently Amended) A photocatalyst composition, which

comprises:

a photocatalyst powder; and

an anionic linear polymer that partially covers a surface of the

photocatalyst powder, said polymer leaving uncovered photocatalyst surface,

wherein the polymer having an anionic group attracts pollutant materials

having a positive charge to the photocatalyst surface, and the polymer is

selected from the group consisting of poly(fluorine-substituted sulfonic acid),

poly(fluorine containing carboxylic acid), polystyrene sulfonic acid, and

polyvinyl sulfonic acid, and wherein said partially covered surface is prepared

by applying a polymer solution in an amount of 0.05 to 5 ml 0.4 ml with a 5%

by weight solution to the photocatalyst surface per gram of the photocatalyst.

16. (Previously Presented) The photocatalyst composition according to

claim 15, wherein the photocatalyst powder has a shape that is spherical, flat,

tubular or fibrous.

17. (Cancelled)

18. (Previously Presented) The photocatalyst composition according to

claim 15, wherein the photocatalyst is selected from the group consisting of

titanium dioxide, zinc oxide, zirconium oxide and tungsten oxide.

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19. (Currently Amended) A high-function photocatalyst having its

surface partially covered with a polymer having an anionic group, wherein the

anionic group attracts pollution materials to the photocatalyst, said polymer

leaving uncovered photocatalyst surface, wherein the polymer having an

anionic group attracts pollutant materials having a positive charge to the

photocatalyst surface, and the polymer is selected from the group consisting of

poly(fluorine-substituted sulfonic acid), poly(fluorine containing carboxylic

acid), polystyrene sulfonic acid, and polyvinyl sulfonic acid, and wherein said

partially covered surface is prepared by applying a polymer solution in an

amount of 0.05 to 5 ml 0.4 ml with a 5% by weight solution to the

photocatalyst surface per gram of the photocatalyst.

20. (Previously Presented) The high-function photocatalyst according

to claim 1, wherein the anionic group attracts pollution materials to the

photocatalyst.

21. (Previously Presented) The method according to claim 7, wherein

the anionic group attracts pollution materials to the photocatalyst.

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22. (Previously Presented) The photocatalyst composition according to claim 15, wherein the anionic group attracts pollution materials to the

photocatalyst.

23-26. (Cancelled)

27. (New) The high-function photocatalyst according to claim 1 or 2,

wherein the photocatalyst is contained in a suspension to decompose the

pollutant materials therein.